

POSTER SESSION (13:30-15:30, Main Hall A, B)

All poster presenters must give the short oral presentations in Short Presentation Session scheduled on September 29, 11:00 - 12:00.
Each Area Session Room; see page 46.

Area 1: Advanced LSI Processing & Materials Science (20 papers)

PS-1-1
Low Interface Trap Density in $\text{In}_{0.53}\text{Ga}_{0.47}\text{As}$ Metal-Oxide-Semiconductor Capacitors with Molecular Beam Deposited $\text{HfO}_2/\text{La}_2\text{O}_3$ High- κ Dielectrics
T.W. Lin¹, J.N. Yao¹, Y.C. Lin¹, K.C. Yang¹, W.H. Wu¹, K. Kakushima², J.S. Maa¹, E.Y. Chang¹ and H. Iwai², ¹NCTU and ²Tokyo Tech (Taiwan)

PS-1-2
Impact of in situ Plasma Enhanced Atomic Layer Deposition on the Electrical Properties of $\text{HfO}_2/\text{In}_{0.53}\text{Ga}_{0.47}\text{As}$ MOSCAPs for Low EOT and Low Interface State Density
Q.H. Luc, H.B. Do, S.P. Cheng, J.H. Chen, S.H. Huynh, P.C. Chang, Y.C. Lin and E.Y. Chang, NCTU (Taiwan)

PS-1-3
Improving Performance of $\text{In}_{0.53}\text{Ga}_{0.47}\text{As}$ Metal-Oxide-Semiconductor Field-Effect-Transistors using in situ Post Remote-Plasma Treatment with N_2/H_2 Gases
Q.H. Luc, S.P. Cheng, J.H. Chen, G.Y. Lin, H.B. Do, P.C. Chang, G.W. Huang, K.M. Chen, Y.C. Lin and E.Y. Chang, NCTU (Taiwan)

PS-1-4
Improved Interface of $\text{HfO}_2/\text{InGaAs}$ MOS by Employing Thin SiN_x Interfacial Layer using Plasma Enhanced Atomic Layer Deposition
S.K. Eom¹, R.S. Ki¹, D.H. Kim¹, H.Y. Cha² and K.S. Seo¹, ¹Seoul National Univ. and ²Hongik Univ. (Korea)

PS-1-5
Sub-0.2V Switching Voltage of Negative Capacitance Double Gate Tunnel FET using Ferroelectric Gate
M.H. Lee¹, C. Liu¹, P.G. Cheng¹, C.C. Cheng¹, K.Y. Chu¹, M.J. Xie¹, S.N. Liu¹, J.W. Lee¹, S.J. Huang¹ and M.H. Liao², ¹National Taiwan Normal Univ. and ²National Taiwan Univ. (Taiwan)

PS-1-6
Fabrication of Low-Temperature (< 400 °C) Germanium MOSCAPs by Microwave Thermal Oxidation
W.C. Chi¹, C.C. Hsu^{1,2}, C.H. Chou¹, A.S. Shih¹, Y.J. Lee² and C.H. Chien¹, ¹NCTU and ²NDL, NARLabs (Taiwan)

PS-1-7
High-Performance P-Channel Polycrystalline-Germanium Thin Film Transistors via Excimer Laser Crystallization and Counter Doping
C.Y. Liao, C.Y. Huang, M.H. Huang, C.H. Chou and H.C. Cheng, NCTU (Taiwan)

PS-1-8
UV Raman and Multiwavelength Photoluminescence Characterization of Ion Implanted Silicon for In-Line Dopant Activation Process Monitoring Applications
W.S. Yoo¹, T. Ishigaki¹, T. Ueda¹, K. Kang¹, N. Hasuike², H. Harima² and M. Yoshimoto², ¹WaferMasters, Inc. and ²KIT (USA)

PS-1-9
Influence of in-situ Sb-Doping on Crystalline and Electrical Characteristics of n-type $\text{Ge}_{1-x}\text{Sn}_x$ Epitaxial Layer
J. Jeon¹, T. Asano^{1,2}, W. Takeuchi¹, M. Kurosawa^{1,3}, O. Nakatsuka¹ and S. Zaima^{1,3}, ¹Nagoya Univ., ²JSPS Research Fellow and ³EcoTopia Sci. Inst., Nagoya Univ. (Japan)

PS-1-10
 $n^+ \text{Si/pGe}$ Cross Heterojunctions Fabricated by Narrow Membrane Bonding
T.C. Liu^{1,2}, S. Kabuyanagi^{1,2}, T. Nishimura^{1,2} and A. Toriumi^{1,2}, ¹Univ. of Tokyo and ²JST-CREST (Japan)

PS-1-11
PtGe-Source/Drain Ge p-MOSFET with High On/Off Ratio and Low Parasitic Resistance
S. Tanaka, Y. Nagatomi, Y. Nagaoka, K. Yamamoto, D. Wang and H. Nakashima, Kyushu Univ. (Japan)

PS-1-12
Impact of Ultra-high Sn Content $\text{Sn}_x\text{Ge}_{1-x}$ Interlayer on Reducing Schottky Barrier Height at Metal/n-Ge Interface
A. Suzuki¹, O. Nakatsuka¹, S. Shibayama^{1,2}, M. Sakashita¹, W. Takeuchi¹, M. Kurosawa^{1,3} and S. Zaima^{1,3}, ¹Nagoya Univ., ²JSPS Research Fellow and ³EcoTopia Sci. Inst., Nagoya Univ. (Japan)

PS-1-13
Introduction of SiGe/Si Heterojunction into Novel Multilayer Tunnel FinFETs
Y. Morita, T. Mori, K. Fukuda, W. Mizubayashi, S. Migita, K. Endo, S. O'uchi, Y.X. Liu, M. Masahara, T. Matsukawa and H. Ota, AIST (Japan)

PS-1-14
Observation of Plastic and Elastic Deformations in Ge Films of Bonded GeOI
T. Nishimura, T. Nakamura, T. Yajima and A. Toriumi, Univ. of Tokyo (Japan)

PS-1-15
Formation of Single Crystalline Silicon with Midair Cavity for Meniscus Force-Mediated Local Layer Transfer and Fabrication of High-Performance MOSFETs on Insulator
M. Akazawa, S. Takeshima, A. Nakagawa, K. Hiramatsu and S. Higashi, Hiroshima Univ. (Japan)

PS-1-16
Comprehensive Characterization of Generated Trap Sites in Gate Insulator using Advanced Stress-induced Leakage Current Simulator
Y. Higashi, J. Chen and T. Ishihara, Toshiba Corp. (Japan)

PS-1-17
First-Principles Study on Hydrogen Annealing Effect in Si/SiO_2 Interface by Thermal Oxidation
S. Kawachi¹, H. Hiroki¹, M. Araidai¹, H. Kageshima^{2,4}, T. Endoh^{3,4} and K. Shiraishi^{1,4}, ¹Nagoya Univ., ²Shimane Univ., ³Tohoku Univ. and ⁴JST-ACCEL (Japan)

PS-1-18
Angle-resolved Photoelectron Spectroscopy Studies of Initial Stage of Thermal Oxidation on 4H-SiC (0001)
H. Arai and H. Nohira, Tokyo City Univ. (Japan)

PS-1-19 (Late News)
Investigation and Comparison of Quantum-Capacitance Induced Inversion-Charge Loss for Ultra-Thin-Body and Double-Gate III-V n-MOSFETs
S.L. Shen, H.H. Shen, C.H. Yu and P. Su, NCTU (Taiwan)

PS-1-20 (Late News)
New Structural Properties of Ferroelectric Y_2O_3 -doped HfO_2 Films Probed by Microscopic Raman Spectroscopy Measurements
K. Izukashi^{1,2}, T. Nishimura^{1,2}, S. Migita^{2,3} and A. Toriumi^{1,2}, ¹Univ. of Tokyo, ²AIST and ³JST-CREST (Japan)

Area 2: Interconnect Technologies and 3D Integration/ Sensor/ MEMS Integration/ Materials and Characterization (18 papers)

PS-2-1
Mechanical Properties of Electrodeposited Gold for MEMS Device
M. Yoshiba^{1,2}, C.Y. Chen^{1,2}, T.F.M. Chang^{1,2}, D. Yamane^{1,2}, K. Machida^{1,2,3}, K. Masu^{1,2} and M. Sone^{1,2}, ¹Tokyo Tech, ²JST-CREST and ³NTT AT (Japan)

PS-2-2
Proposal of a Simple MEMS Phase Shifter Based on Effective Dielectric Constant Modulation
D. Nakano¹, M. Mori¹, K. Maezawa¹, H. Ishii² and H. Ando³, ¹Univ. of Toyama, ²Toyohashi Univ. of Tech. and ³National Inst. of Tech., Toyota College (Japan)

PS-2-3
Study on Ti/Au Two-Layered Cantilevers with Different Aspect Ratio for MEMS Devices
M. Teranishi^{1,2}, T.F.M. Chang^{1,2}, C.Y. Chen^{1,2}, T. Konishi³, K. Machida^{1,2,3}, H. Toshiyoshi^{1,4}, D. Yamane^{1,2}, K. Masu^{1,2} and M. Sone^{1,2}, ¹JST-CREST, ²Tokyo Tech, ³NTT AT and ⁴Univ. of Tokyo (Japan)

PS-2-4
Micro-Texture Dependence of the Strength of Electroplated Copper Fine Bumps Used for 3-Dimensional Integration
M. Gotoh, K. Suzuki and H. Miura, Tohoku Univ. (Japan)

PS-2-5
Local Stress Effect Due to Operation-Heating-Induced Adhesive Expansion on Transistor Performances in 3D IC
H. Kino, H. Hashiguchi, S. Tanikawa, Y. Sugawara, S. Ikegaya, T. Fukusima, M. Koyanagi and T. Tanaka, Tohoku Univ. (Japan)

PS-2-6
Combined Surface-Activated Bonding Technique for Low-Temperature Hydrophilic Wafer Bonding with Interfacial Water Management
R. He¹, M. Fujino¹, A. Yamauchi² and T. Suga¹, ¹Univ. of Tokyo and ²Bondtech Co., Ltd. (Japan)

PS-2-7
Transient Liquid-Phase Sintering using Tin and Silver Powder Mixture for Die Bonding
M. Fujino¹, H. Narusawa¹, Y. Kuramochi¹, E. Higurashi¹, T. Suga¹, T. Shiratori² and M. Mizukoshi³, ¹Univ. of Tokyo, ²ALPHA DESIGN CO., LTD. and ³SYNDEO (Japan)

PS-2-8
A Novel Hybrid Strategy of via-first Bare TSVs for Enhanced Signal Integrity in 3-D Integrated Systems
R. Fang¹, X. Sun¹, M. Miao² and Y. Jin¹, ¹Peking Univ. and ²Beijing Info. Sci.&Tech. Univ. (China)

PS-2-9
Capacitance Characteristics of Low- κ Low-Cost CVD Grown Polyimide Liner for High-Density Cu-TSVs in 3D-LSI
M. Murgesan, J.C. Bea, T. Fukushima, H. Hashimoto, K.W. Lee and M. Koyanagi, Tohoku Univ. (Japan)

PS-2-10
Improving Step Coverage of PVD Barrier/Seed through Bias Power Alternation for High Aspect Ratio TSVs
S. Yang¹, W. Cheng¹, H. Wu¹, C. Song^{1,2} and W. Zhang^{1,2}, ¹NCAP China and ²IMECAS (China)

PS-2-11
Thermal Mechanical Behavior of TSVs with WN/Ni as Barrier/Seed Layer System for 2.5D Integration
X.M. Jing, NCAP China (China)

PS-2-12

Electroless Nickel Barrier/Seed Layer Deposition on Dielectric Liners for Advanced Cu-TSV Applications

T. Fukushima¹, K. Taniguchi², S. Watariguchi², M. Murugesan¹, C. Nagai¹, A. Nakamura¹, H. Hiroyuki¹, J. Bea¹, T. Tanaka¹, M. Koyanagi³ and K. Lee¹, ¹Tohoku Univ. and ²Meltex Inc. (Japan)

PS-2-13

A Novel Low Temperature (<500°C) and Low-κ (3.8) Boron Nitride PECVD Offset Spacer Featuring 3D VLSI Integration

C.M.V. Lu^{1,2}, C. Bout¹, C. Fenouillet Beranger¹, A. Roule¹, M.P. Samson^{1,2}, B. Previtali¹, C. Arvet^{1,2}, A. Michallet^{1,2}, N. Rochat¹, S. Favier^{1,2}, R. Kachtouli¹, V. Loup¹, P. Besson^{1,2}, M. Garcia Barros^{1,2}, N. Posseme¹, F. Pierre¹, P. Maury², D. Benoit¹, P. Batude¹, M. Vinet¹ and T. Skotnicki², ¹CEA-LETI and ²STMicroelectronics (France)

PS-2-14

Impact and Improvement of Resistor Process Variation on RF Passive Circuit Design in Integrated Passive Devices (IPD) Technology

Y.C. Chang^{1,2}, P.Y. Wang¹, S.H. Hsu¹, Y.T. Chang³, C.K. Chen³ and D.C. Chang², ¹National Tsing Hua Univ., ²CIC, NARLabs and ³BSMI, MOEA (Taiwan)

PS-2-15

Preparation of High Performance SiN_x Films Deposited by Reactive Sputtering and PECVD at Low Temperatures

M. Sato¹, M.B. Takeyama¹, Y. Nakata², Y. Kobayashi², T. Nakamura² and A. Noya¹, ¹Kitami Inst. of Tech. and ²Fujitsu Labs. Ltd. (Japan)

PS-2-16

In Situ FTIR Spectroscopic and Kinetic Studies of Cu Surface Reduction by Using Formic Acid Treatment with Pt Catalysts

P.W. Chou¹, C.C. Kuo¹, J.Y. Lin² and J.M. Song¹, ¹National Chung Hsing Univ. and ²ITRI (Taiwan)

PS-2-17

Measurement of the Strength at Grain Boundaries in Electroplated Copper Thin-Film Interconnections

T. Nakanishi, T. Kato, Y. Ichikawa, K. Suzuki and H. Miura, Tohoku Univ. (Japan)

PS-2-18 (Late News)

Radio Frequency Characteristics in Tantalum Nitride Thin Film Resistor

S.H. Kwon¹, M. Nam¹, A. Kim¹, K. Kang¹, S.J. Chae¹, S.J. Lee¹, W.S. Sul¹ and S.G. Pyo¹, ¹Chung-Ang Univ. and ²NNFC (Korea)

Area 3: CMOS Devices / Device Physics

(17 papers)

PS-3-1

Discrete Dopant Impact on the 7 nm Nanowire Transistor Performance

X. Wang¹, Y. Wang², C. Ridder¹, E. Towie², B. Cheng³, X. Liu² and A. Asenov^{1,3}, ¹Univ. of Glasgow, ²Peking Univ. and ³Gold Standard Simulations Ltd. (UK)

PS-3-2

Proposal of Tunneling and Diffusion Current Hybrid MOSFET

K. Furukawa, R. Kuroda, T. Suwa, K. Hashimoto, A. Teramoto and S. Sugawa, Tohoku Univ. (Japan)

PS-3-3

RF Characteristics of Poly-Si TFTs with HfO₂ Gate Dielectric Fabricated by Microwave Annealing

J.J. Tsai and H.H. Hu, National Taipei Univ. of Tech. (Taiwan)

PS-3-4

Trap-Assisted Tunneling Effects on Gate-Induced Drain Leakage in Silicon-Germanium Channel pFET

V.A. Tiwari¹, A. Scholze², R. Divakaruni² and D.R. Nair¹, ¹Indian Inst. of Tech. Madras and ²IBM SRDC (India)

PS-3-5

Low Frequency Noise and Mobility Correlation from RT to Low Temperatures for n-Channel Ge MOSFETs

S. Ghosh, P. Bhatt, Y. Tiwari and S. Lodha, IIT Bombay (India)

PS-3-6

Comparison of Gate Structures of P-channel Poly-Si Nanowire Trench Ultra-thin Channel Juntionless Field-Effect Transistors

Y.C. Wu¹, K.W. Lin¹, M.S. Yeh¹, Y.R. Lin¹, M.H. Wu¹ and Y.H. Lin², ¹National Tsing Hua Univ. and ²National United Univ. (Taiwan)

PS-3-7

1/f Noise Performances and Noise Sources of Accumulation Mode Si(100) n-MOSFETs

P. Gaubert, A. Teramoto and S. Sugawa, Tohoku Univ. (Japan)

PS-3-8

ON Current Enhancement of Nanowire Schottky Barrier Tunnel FET

K. Takei¹, S. Hashimoto¹, J. Sun¹, X. Zhang¹, S. Asada¹, T. Xu¹, T. Wakamizu¹, T. Matsukawa², M. Masahara² and T. Watanabe¹, ¹Waseda Univ. and ²AIST (Japan)

PS-3-9

Novel 5-State Latch Using Double-Peak Negative Differential Resistance (NDR) and Standard Ternary Inverter (STI)

S. Shin and K.R. Kim, UNIST (Korea)

PS-3-10

Impacts of Threshold Voltage Design for Monolithic 3D 6T SRAM with Si and InGaAs-n/Ge-p Devices considering Interlayer Coupling

K.C. Yu, C.H. Yu, V.P.H. Hu, P. Su and C.T. Chuang, NCTU (Taiwan)

PS-3-11

Multi-Threshold Voltages in Ultra-thin-body Devices by Asymmetric Dual-Gate Structure

H. Kim, J. Park, M.W. Kwon, S. Hwang and B.G. Park, Seoul National Univ. (Korea)

PS-3-12

Investigation of Trap Properties in High-k/Metal Gate pMOSFETs of Higher Al Energy and Concentration Ion Implantation on Random Telegraph Noise

T.H. Kao¹, S.J. Chang¹, Y.K. Fang¹, P.C. Huang¹, Y.K. Su¹, Y.J. Shen¹, C.Y. Wu² and S.L. Wu², ¹NCKU and ²Cheng Shiu Univ. (Taiwan)

PS-3-13

The Limits of Applicability of the Analytic Model for Hot Carrier Degradation

M. Jech¹, P. Sharma¹, S. Tyaginov^{1,2}, F. Rudolf¹ and T. Grasser¹, ¹TU Wien and ²Ioffe Physical-Techn. Inst. (Austria)

PS-3-14

Investigation of Backgating Effect on Superlinear Onset of Output Characteristics for UTB III-V Heterojunction Tunnel FET

S.E. Huang, M.L. Fan and P. Su, NCTU (Taiwan)

PS-3-15

Optimized Nanowire Diameter for III-V Homojunction and Heterojunction Gate-All-Around Tunnel FETs

Y.W. Wang and P. Su, NCTU (Taiwan)

PS-3-16

Transmission Line Model and Transconductance Method for Layout Dependent Source Resistance Extraction in Multi-Finger MOSFETs

Y.Z. Lo and J.C. Guo, NCTU (Taiwan)

PS-3-17

Comparative Study of Tunnel Field Effect Transistors with Dopant-Segregated Schottky Source/Drain

Y.B. Zhang, L. Sun, H. Xu and J.W. Han, Peking Univ. (China)

Area 4: Advanced Memory Technology

(13 papers)

PS-4-1

Si-based Nonvolatile Field Effect Transistor using Low Temperature Process

Y. Miyata, A. Ashida, T. Yoshimura and N. Fujimura, Osaka Prefecture Univ. (Japan)

PS-4-2

Transition Metal Complex Reaction Etching for MRAM Applications using Neutral Beam and Its Mechanism Investigated by First-Principles Calculation

T. Kubota¹, Y. Kikuchi^{1,2}, T. Nozawa² and S. Samukawa^{1,3}, ¹IFS, Tohoku Univ., ²Tokyo Electron Ltd. and ³WPI-AIMR, Tohoku Univ. (Japan)

PS-4-3

A 16-Level-Cell Memory with 0.24mV/°C Temperature Characteristics Comprising Crystalline In-Ga-Zn Oxide FET

T. Matsuzaki, T. Onuki, S. Nagatsuka, H. Inoue, T. Ishizu, Y. Ieda, N. Yamade, H. Miyairi, M. Sakakura, Y. Shionoiri, K. Kato, T. Okuda, J. Koyama, Y. Yamamoto and S. Yamazaki, Semiconductor Energy Lab. Corp. Ltd. (Japan)

PS-4-4

High-performance In-Ga-Zn-O TFT Memory with Pt Nanocrystals

S.B. Qian, W.P. Zhang, W.J. Liu and S.J. Ding, Fudan Univ. (China)

PS-4-5

Resistance Switching Memory Operation of CaF₂/Si/CaF₂ Resonant-tunneling Quantum-well Structures using Nanocrystalline-Si Secondary Barrier Layers

K. Suda, Y. Kuwata and M. Watanabe, Tokyo Tech (Japan)

PS-4-6

Switching Kinetics of VCM-based Memristor: Evolution and Positioning of Nanofilament

J.Y. Chen, C.W. Huang, C.H. Chiu, Y.T. Huang and W.W. Wu, NCTU (Taiwan)

PS-4-7

Impact of Film Morphology on the Switching Characteristics of Ta₂O₅-Based Atomic Switches

C. Mannequin¹, T. Tsuruoka¹, T. Hasegawa² and M. Aono¹, ¹NIMS and ²Waseda Univ. (Japan)

PS-4-8

Guideline Model for the Bias-Scheme-Dependent Power Consumption of a ReRAM Crossbar Array

W.K. Sun, H. Lim, S.J. Choi and H.S. Shin, Ewha Womans Univ. (Korea)

PS-4-9

Properties of SiC Resistive Memory for Harsh Environments

K. Morgan, J. Fan, R. Huang, L. Zhong, R. Gowers, L. Jiang and K. De Groot, Univ. of Southampton (UK)

PS-4-10

Understanding of the Abnormal Unipolar Resistance Switching Behavior in CBRAM

H.T. Sun, Q. Liu, D.L. Xun, K.K. Zhang, H.B. Lv, W. Banerjee, S.B. Long and M. Liu, IMECAS (China)

PS-4-11
SONNOS Nonvolatile Memory Based on Ultra-Thin Body Poly-Si Junctionless Field-Effect Transistor with Excellent Retention
Y.R. Lin¹, W.C. Wang¹, Y.H. Lin² and Y.C. Wu¹, ¹National Tsing Hua Univ. and ²National United Univ. (Taiwan)

PS-4-12 (Late News)
Concept of a SOT-MRAM Based on 1Transistor-1MTJ-Cell Structure
A. Makarov, T. Windbacher, V. Sverdlov and S. Selberherr, TU Wien (Austria)

PS-4-13 (Late News)
Theoretical Study of SET Operation in Nantero Memory Cell
M. Stopa^{1,2} and T. Rueckes¹, ¹MIT and ²Nantero Inc. (USA)

Area 5: Advanced Circuits and Systems

(12 papers)

PS-5-1
Associative Memory for Nearest Neighbor Search with High Flexibility of Reference-Vector Number Due to Configurable Dual-Storage Space
F. An, K. Mihara, S. Yamasaki, L. Chen and H.J. Mattausch, Hiroshima Univ. (Japan)

PS-5-2
Memory-based LVQ Neural Network with Dedicated Learning Circuit
X. Zhang, F. An, L. Chen and H.J. Mattausch, Hiroshima Univ. (Japan)

PS-5-3
Non-volatile and Volatile Hybrid Memories Embedded in the Standard CMOS Process
H. Lin, Y.L. Chiou, H.J. Chiu and C.Y. Wu, National Chung Hsing Univ. (Taiwan)

PS-5-4
A Compact 0.3-to-1.125GHz Self-Biased PLL for System-on-Chip Clock Generation in 0.18μm CMOS
Z. Zhang, L. Liu, P. Feng, J. Liu and N. Wu, Chinese Academy of Sciences (China)

PS-5-5
A DC-balanced Bus-invert Coding for Stabilizing the Intermediate Power Level in Stacked-Vdd LSIs
Y. Kohara, N. Kubo, M. Alimudin, A. Rahmat and K. Nakamura, Kyushu Inst. of Tech. (Japan)

PS-5-6
A Wireless Power Transfer System for Small-Sized Sensor Applications
Y. Akihara¹, T. Hirose¹, Y. Tanaka¹, N. Kuroki¹, M. Numa¹ and M. Hashimoto², ¹Kobe Univ. and ²Osaka Univ. (Japan)

PS-5-7
Batteryless Transmitter for Biomedical Implant
H.C. Chen, C.Y. Kao and S.C. Yang, National Taiwan Univ. of Sci. and Tech. (Taiwan)

PS-5-8
A Fully On-Chip Switched-Capacitor DC-DC Power Converter with Startup/Fail-Safe Circuit
Y. Kojima, T. Hirose, K. Tsubaki, T. Ozaki, H. Asano, N. Kuroki and M. Numa, Kobe Univ. (Japan)

PS-5-9
A Fully Integrated Boost Power Supply with On-Chip Photovoltaic Device
A. Watanabe, D. Orihara, Y. Minami and N. Nakano, Keio Univ. (Japan)

PS-5-10
Discharging-Phototransistor-Integrated High-Voltage Si Photovoltaic Cells for Fast Driving of an Electrostatic MEMS Actuator by Wavelength Modulation
I. Mori and Y. Mita, Univ. of Tokyo (Japan)

PS-5-11
Design and Characteristics of a MEMS Human Body Hardness Sensor Aimed to Diagnosis of Lesion Size
Y. Maeda, K. Terao, F. Shimokawa and H. Takao, Kagawa Univ. (Japan)

PS-5-12
CMOS Temperature Sensor Using a Modified Bandgap Reference Voltage Circuit with a Low-Temperature-Coefficient Resistor Structure
R.L. Wang¹, J.L. Shi¹, Y.F. Hao¹, K.B. Lee¹, X.J. Yang¹, W.D. Wu¹, H.H. Liao², H.H. Tsai² and Y.Z. Juang², ¹National Kaohsiung Normal Univ. and ²NARLabs (Taiwan)

Area 6: Compound Semiconductor Electron Devices & Related Technologies

(27 papers)

PS-6-1
Accuracy of Recessed Gate for GaN Power FETs and High Temperature Capability of Diamond Heat Sink
Y.T. Kim¹, J.H. Lee² and Y.M. Jhon¹, ¹Korea Inst. of Sci. & Tech. and ²KNU (Korea)

PS-6-2
Enhancement Mode AlGaIn/GaN MIS-HEMTs Using Multilayer HfO₂/La₂O₃ Gate Insulator for High Power Application
Y.X. Huang¹, W.C. Shih¹, T.W. Lin¹, C.H. Wu¹, Y.C. Lin¹, J.S. Maa¹, E.Y. Chang¹, K. Kakushima² and H. Iwai², ¹NCTU and ²Tokyo Tech (Taiwan)

PS-6-3
Improved Linearity and Reliability in GaN MOS-HEMTs Using Nanolaminate La₂O₃/SiO₂ Gate Dielectric
W.C. Shih¹, H.H. Hsu¹, Y.X. Huang¹, T.W. Lin¹, C.H. Wu¹, Y.C. Lin¹, J.S. Maa¹, E.Y. Chang¹, K. Kakushima² and H. Iwai², ¹NCTU and ²Tokyo Tech (Taiwan)

PS-6-4
Thermal Stability of the Interface between Atomic Layer Deposited High-*k* ZrO₂ and GaN
H. Wang^{1,2}, G. Ye¹ and K.S. Ang², ¹NTU and ²TL@NTU (Singapore)

PS-6-5
Analysis of Electrical Characteristics of AlGaIn/GaN on Si Large SBD by Changing Structure
H.S. Lee^{1,2}, D.Y. Jung¹, Y.R. Park¹, J.H. Na¹, H.G. Jang¹, H. Lee¹, C.H. Jun¹, J.B. Park¹, Z.S. Kim¹, J.K. Mun¹, S.O. Ryu², S.C. Ko¹ and E.S. Nam¹, ¹Electronics and Telecommunications Res. Inst. and ²Dankook Univ. (Korea)

PS-6-6
Electrolyte Electro-Reflectance Spectra of Crack-Free AlGaIn/GaN High Electron Mobility Transistors on Si Substrate
T.S. Ko¹, B.Y. Hu¹, N.W. Chang¹, D.Y. Lin¹ and J.S. Li², ¹National Univ. of Changhua Edu. and ²Feng Chia Univ. (Taiwan)

PS-6-7
Study of AlGaIn/GaN Tri-Gate HEMTs for Device Performance Improvement
C.C. Liu¹, Y.X. Huang¹, W.C. Shih¹, H.H. Hsu¹, Y.C. Lin¹, J.S. Maa¹, E.Y. Chang¹ and H. Iwai², ¹NCTU and ²Tokyo Tech (Taiwan)

PS-6-8
The Si-Implanted Source/Drain of GaN-based High Electron Mobility Transistors by Using Stacking AlN Protection Layers
A.J. Tzou¹, D.H. Hsieh¹, J.K. Huang¹, C.J. Su², Z.Y. Li^{1,3}, C.Y. Chang^{1,4} and H.C. Kuo¹, ¹NCTU, ²NDL, NARLabs, ³Epistar Inc. and ⁴Academia Sinica (Taiwan)

PS-6-9
High Performance of AlGaIn/GaN HEMT Device with Embedded Multiple Graphene Layers
C.Y. Lee¹, Y.P. Lan², Y.S. Gau³, C.H. Chen³, R.M. Lin³ and C.Y. Chang^{1,2}, ¹Academia Sinica, ²NCTU and ³Chang Gung Univ. (Taiwan)

PS-6-10
2-Dimensional Characterization of Ion-Implantation Damage in GaN Schottky Contacts Using Scanning Internal Photoemission Microscopy
K. Shiojima¹, S. Murase¹, S. Yamamoto¹, T. Mishima² and T. Nakamura², ¹Univ. of Fukui and ²Hosei Univ. (Japan)

PS-6-11
DC Characteristics in Nearly Lattice-Matched InAlN/AlGaIn Heterostructure Field-Effect Transistors
T. Tsutsumi, G. Nishino, J. Freedman, M. Miyoshi and T. Egawa, Nagoya Inst. of Tech. (Japan)

PS-6-12
High-Quality PECVD SiO₂ Gate Oxide for Use in Normally-Off AlGaIn/GaN Recessed MOS-HFETs
H.S. Kim¹, J.G. Lee², S.H. Park¹, S.W. Han¹, K.S. Seo³ and H.Y. Cha¹, ¹Hongik Univ., ²Univ. of Texas at Dallas and ³Seoul National Univ. (Korea)

PS-6-13
Analysis of Post-Deposition Annealing Effects on Insulator/Semiconductor Interface of Al₂O₃/AlGaIn/GaN High-Electron-Mobility Transistors on Si Substrates
T. Kubo, M. Miyoshi and T. Egawa, Nagoya Inst. of Tech. (Japan)

PS-6-14
High Thermal Stability AlGaIn/GaN Schottky Barrier Diode with Diamond-Like Carbon (DLC) Heat Dissipation Anode Design
Y.H. Cheng, H.Y. Wang, L.Y. Peng and H.C. Chiu, Chang Gung Univ. (Taiwan)

PS-6-15
Nonvolatile Memory Effects in GaN Metal-Oxide-Semiconductor Heterostructure FETs with Thin AlGaIn Barrier
D.M. Keum, K.H. Cho and H.T. Kim, Hongik Univ. (Korea)

PS-6-16
Low Current Collapsed AlGaIn/GaN HEMT-on-Si Substrate with SiN_x / HfO₂ Dual Passivation Layer
D.H. Kim¹, M.J. Kang¹, S.K. Eom¹, H.Y. Cha² and K.S. Seo¹, ¹Seoul National Univ. and ²Hongik Univ. (Korea)

PS-6-17
Preparation of InAs Surface by Hydrogen Plasma Pre-Treatment for Low Interfacial Trap Density MOS Capacitors
C. Y. Chen¹, C.H. Hsieh¹, W.J. Hsueh¹ and J.I. Chyi^{1,2}, ¹National Central Univ. and ²Academia Sinica (Taiwan)

PS-6-18
Analysis of Energy States Where Electrons and Holes Coexist in Pseudomorphically Strained InAs HEMTs
Y. Nishio, T. Sato, N. Hirayama, T. Iida and Y. Takanashi, Tokyo Univ. of Science (Japan)

PS-6-19
Low Interface Trap Density HfO₂/Al₂O₃/InAs MOS Capacitors Prepared by Nitrogen Plasma Treatment
G.B. He¹, W.J. Hsueh¹, C.Y. Chen¹ and J.I. Chyi^{1,2}, ¹National Central Univ. and ²Research Center for Applied Sci., Academia Sinica (Taiwan)

PS-6-20
Study on Electrical Performances of ZnO-TFTs with 3-D Finlike Channels Fabricated by Nanoimprint Lithography and Atomic Layer Deposition
H.J.H. Chen¹, B.L. Yeh¹, C.Y. Chiang², T.N. Lee¹ and K.C. Hsieh², ¹National Chi Nan Univ. and ²National Tsing Hua Univ. (Taiwan)

PS-6-21
Structural Properties and Electrical Characteristics of High- κ Lu_2O_3 and Lu_2TiO_5 Gate Dielectrics for InGaZnO Thin-Film Transistors
T.M. Pan, C.H. Chen, H.J. Wang and I.C. Huang, Chang Gung Univ. (Taiwan)

PS-6-22
Impact of Gate Dielectrics and Oxygen Annealing on Tin-Oxide Thin-Film Transistors
C.W. Zhong¹, H.C. Lin¹, J.R. Tsai², K.C. Liu³ and T.Y. Huang¹, ¹NCTU, ²Asia Univ. and ³Chang Gung Univ. (Taiwan)

PS-6-23
Mobility Improvement Based on Mobility Model of Crystalline In-Ga-Zn-Oxide with High Indium Composition
K. Tsutsui, D. Matsubayashi, N. Ishihara, T. Takasu, S. Matsuda and S. Yamazaki, Semiconductor Energy Lab. Co., Ltd. (Japan)

PS-6-24
ZnO Thin Film Transistor with U-shape Active Layer for High Performance Application
H.J. Yun, Y.M. Kim, S.D. Yang, H.D. Lee and G.W. Lee, Chungnam National Univ. (Korea)

PS-6-25 (Late News)
Design of Drain for Low off Current in GaAsSb/InGaAs Tunnel FETs
S. Iwata¹, W. Lin¹, K. Fukuda^{1,2} and Y. Miyamoto¹, Tokyo Tech and ²AIST (Japan)

PS-6-26 (Late News)
Low-noise Performance of Pseudomorphic InGaAs/InAlAs HEMTs
I. Watanabe¹, A. Endoh^{1,2}, T. Mimura^{1,2} and A. Kasamatsu¹, ¹NICT and ²Fujitsu Labs. (Japan)

PS-6-27 (Late News)
Effect of Temperature on DC and RF Characteristics of Cryogenic InP HEMTs
A. Endoh^{1,2}, I. Watanabe¹, A. Kasamatsu¹, T. Takahashi², S. Shiba², Y. Nakasha², T. Iwai² and T. Mimura^{1,2}, ¹NICT and ²Fujitsu Labs. (Japan)

Area 7: Photonic Devices and Related Technologies	(23 papers)
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PS-7-1
GaN Metal-Insulator-Semiconductor Ultraviolet Detectors with Lanthanum Fluoride (LaF_3) Insulating Layers
C.H. Chen and C.F. Cheng, Cheng Shiu Univ. (Taiwan)

PS-7-2
Performance Enhancement of Blue InGaN Light-Emitting Diodes with p-InGaN/GaN SPS Last Barrier and p-AlGaIn/GaN SPS EBL
P.K. Lin¹, C.K. Wang¹, Y.Z. Chiou¹, S.B. Chang² and S.J. Chang², ¹Southern Taiwan Univ. of Sci. and Tech. and ²NCKU (Taiwan)

PS-7-3
Enhanced Light Intensity of InGaN-based LEDs Grown on Molybdenum Patterned Sapphire Substrates
W.H. Wu¹, Y.H. You², V.C. Su², M.L. Lee², P.H. Chen², C.H. Kuan² and R.M. Lin¹, ¹Chang Gung Univ. and ²National Taiwan Univ. (Taiwan)

PS-7-4
A Narrow-band Short Wavelength Type II InAs/GaSb Superlattices Photodetector with High Performance
J.L. Huang^{1,2}, W.Q. Ma¹, Y.H. Zhang¹, Y.L. Cao¹, K. Liu¹, J.W. Huang¹ and S.L. Lu², ¹Institute of Semiconductors, CAS and ²SINANO, CAS (China)

PS-7-5
Enhanced Responsivity and Detectivity Values of Short 30-period InAs/GaSb Type-II Infrared Photodetectors with Reduced Device Areas
H.A. Chen^{1,2}, T.C. Shih¹, H.Y. Chen³ and S.Y. Lin^{1,2,3}, ¹Academia Sinica, ²National Taiwan Univ. and ³National Taiwan Ocean Univ. (Taiwan)

PS-7-6
Low-resistivity Lateral PIN Junction Formed by Ni-InGaAsP Alloy for Carrier-Injection InGaAsP Photonic Devices
J.K. Park^{1,2}, M. Takenaka^{1,2} and S. Takagi^{1,2}, ¹Univ. of Tokyo and ²JST-CREST (Japan)

PS-7-7
Broadband Gain Superluminescent Diode Based on Self-assembled InAs Quantum Dots with Segmented Contacts
N. Ozaki^{1,2}, T. Yasuda¹, H. Shibata¹, H. Ohsato³, E. Watanabe³, N. Ikeda², Y. Sugimoto³, D.T.D. Childs² and R.A. Hogg², ¹Wakayama Univ., ²Univ. of Sheffield and ³NIMS (Japan)

PS-7-8
Widely Tunable InAs/InP Quantum-Dot External-Cavity Laser with Bent-Waveguide Structure
F. Gao, S. Luo, H.M. Ji and T. Yang, Chinese Academy of Sciences (China)

PS-7-9
Photoconductivity with 1.55 μm Excitation of InAs QDs Embedded in InGaAs Barriers on GaAs Substrate
K. Murakumo, Y. Yamaoka, N. Kumagai, T. Kitada and T. Isu, Tokushima Univ. (Japan)

PS-7-10
Coupling Structures between Crystal/Amorphous Si Waveguides for In-Plane Integration
K. Itoh, Y. Kuno, J. Kang, Y. Hayashi, J. Suzuki, T. Amemiya, N. Nishiyama and S. Arai, Tokyo Tech (Japan)

PS-7-11
Photosensing in MOS(p) and MOS(n) Photodiodes
C.T. Yang and J.G. Hwu, National Taiwan Univ. (Taiwan)

PS-7-12
Free Spectral Range (FSR) Control of a High Quality Factor - 1D Photonic Crystal (PhC) Extended Cavity
A.R. Md Zain¹, B.Y. Majlis¹ and R.M. De La Rue², ¹Universiti Kebangsaan Malaysia and ²Univ. of Glasgow (Malaysia)

PS-7-13
Output Characteristics of a Double Circular Ring Resonators Laser Diode Through Slioton Wave Guiding
M.C. Shih, Y.H. Kao and W.H. Lan, National Univ. of Kaohsiung (Taiwan)

PS-7-14
Highly Fabrication-Tolerant Shallow-Grating Coupler for Robust Coupling to Multimode "Optical Pin"
J. Ushida, M. Tokushima, T. Uemura and K. Kurata, PETRA (Japan)

PS-7-15
Ultracompact, Low-loss Waveguide Polarizer Based on Plasmonics
L. Gao, B. Bai and Z. Zhou, Peking Univ. (China)

PS-7-16
Localized Surface Plasmon-Enhanced Light Emission Output of Amorphous Silicon Quantum Dots Light-Emitting Device with Plasmonic Subwavelength Ag Grating Structure
T.H. Tsai, W.K. Choi and H.Y. Lin, National Taiwan Univ. (Taiwan)

PS-7-17
The Excellent Full-color Micro Display Dominated by RGB Quantum Dots
H.Y. Lin¹, H.V. Han¹, W.C. Chong², J.R. Li¹, C.C. Lin¹, H.M. Chen¹, K.M. Lau² and H.C. Kuo¹, ¹NCTU and ²HKUST (Taiwan)

PS-7-19
Enhanced Light Extraction from Lateral Side of InGaN-based LEDs Grown on Nano-Sized Patterned Sapphire Substrates
Y.H. You¹, W.H. Wu², B.W. Lin², W.C. Hsu¹, V.C. Su¹, M.L. Lee¹, P.H. Chen¹, C.H. Kuan¹ and R.M. Lin¹, ¹National Taiwan Univ., ²Chang Gung Univ., ³NCTU and ⁴Sino-America Silicon Products Inc. (Taiwan)

PS-7-20
Hydrothermal Growth of Single-crystalline ZnO Thin Films and Theirs Application on UV Photodetectors
C.H. Wu¹, S.J. Wang¹, T.H. Lin¹, Y.C. Tu¹, C.H. Hung¹, P.Y. Liu¹, Y.H. Chin¹, K.M. Uang² and T.M. Chen², ¹NCKU and ²WuFeng Univ. (Taiwan)

PS-7-21
Preparation of Porous p-ZnO Films by Hydrothermal Method and Its Application on Ultraviolet Sensors
Y.C. Tu¹, S.J. Wang¹, T.H. Lin¹, C.H. Hung¹, C.H. Wu¹, P.Y. Liu¹, Y.H. Chin¹, K.M. Uang² and T.M. Chen², ¹NCKU and ²WuFeng Univ. (Taiwan)

PS-7-22
Electro-Optic Characteristics Improvement of ZnMgTe/ZnTe Waveguide Devices
W.C. Sun¹, F. Kazami¹, J. Wang¹, T. Nakasu¹, S. Hattori², T. Kizu¹, Y. Hashimoto¹, M. Kobayashi^{1,2} and T. Asahi², ¹Waseda Univ., ²Kagami Memorial Res. Inst. for Materials Sci. and Tech. and ³JX Nippon Mining & Metals Corp. (Japan)

PS-7-23
Demonstration of Spatial Demultiplexing of Polarization Modulation Signal Based on Magneto-optical Modulation of Multiplexed Lightwave in Fiber
K. Nishibayashi¹, H. Yoneda², K. Kuga² and H. Munekata¹, ¹Tokyo Tech, ²Univ. of Electro-Communications and ³NHK STRL (Japan)

PS-7-24
Fabrication of Mesa-type Mg_2Si Pn-junction Photodiode for 2 - 4 μm IR-detection
T. Akiyama, N. Hori and H. Udono, Ibaraki Univ. (Japan)

Area 8: Advanced Material Synthesis and Crystal Growth Technology	(27 papers)
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PS-8-1
Temperature-Dependent Photoluminescence and Hall-Effect Studies of $\text{Ge}_{1-x}\text{Sn}_x$ Alloys Grown on Ge-Buffered Si Substrates
M.Y. Ryu¹, T.R. Harris², B. Wang^{2,3}, Y.K. Yeo² and J. Kouvetakis⁴, ¹Kangwon National Univ., ²AFIT, ³Wright State Univ. and ⁴Arizona State Univ. (Korea)

PS-8-2
Electrical Property of Single-phase HMS Grown by Temperature Gradient Solution Growth Method using Ga and Sn Solvent
S. Hori¹, M. Iioka¹, S. Jimba¹, Y. Hara² and H. Udono¹, ¹Ibaraki Univ. and ²Ibaraki College of Tech. (Japan)

PS-8-3
Surface Hydrogen Passivation and Sn Distribution in $\text{Ge}_{1-x}\text{Sn}_x$ (001) Materials: A DFT Study
H. Johll¹, M. Samuel¹, R.Y. Koo¹, H.C. Kang^{2,3}, S.W. Ong³, Y.C. Yeo² and E.S. Tok^{2,3}, ¹National Junior College, ²NUS and ³Yale-NUS College (Singapore)

PS-8-4
Role of Monolayer Indium Atom Distribution in Metalorganic Chemical Vapor Deposition of InAs/GaAs Epitaxy on Ge Substrate
H.W. Yu, H.Q. Nguyen, T.M. Wang and E.Y. Chang, NCTU (Taiwan)

PS-8-5
Resonant Excitation of Single Luminescence Centers in GaAs:N
M. Ikezawa¹, N. Yasuda¹, L. Zhang¹, Y. Sakuma², K. Sakoda² and Y. Masumoto¹, ¹Univ. of Tsukuba and ²NIMS (Japan)

PS-8-6
Free Exciton Emission from Hexagonal Boron Nitride Films Grown on Sapphire Substrates by Low Pressure Chemical Vapor Deposition
N. Umehara, A. Masuda, T. Shimizu, T. Kouno, H. Kominami and K. Hara, Shizuoka Univ. (Japan)

PS-8-7
N-face GaN (000-1) Films with Hillock-Free Smooth Surfaces Grown by Group-III-Source Flow-Rate Modulation Epitaxy
C.H. Lin, T. Akasaka and H. Yamamoto, NTT Corp. (Japan)

PS-8-8
Heteroepitaxial Growth of GaSb Films on Si(111)-√3×√3-Ga Surface Phase
H. Shimoyama, M. Mori and K. Maezawa, Univ. of Toyama (Japan)

PS-8-9
Selective-Area Growth of Heavily N-Doped C-GaN/GaAs Nanostubs on Si(100) Substrate by Molecular Beam Epitaxy
Y.J. Chang, B. Beekley, M. Goorsky and J. Woo, UCLA (USA)

PS-8-10
AlGaN Microdisks on Top of Supporting GaN Columns Fabricated using Hydrogen Environment Anisotropic Thermal Etching
S. Suzuki¹, T. Kouno¹, H. Takeshima¹, A. Kikuchi², K. Kishino², M. Sakai³ and K. Hara¹, ¹Shizuoka Univ., ²Sophia Univ. and ³Univ. of Yamanashi (Japan)

PS-8-11
Effects of Double-cap Technique on the Improvement of InAs/InAlGaAs/InP Quantum Dots Grown by Metal-organic Chemical Vapor Deposition
B. Shi and K.M. Lau, The Hong Kong Univ. of Sci. & Tech. (China)

PS-8-12
Effect of Remote Doping on Photoluminescence and Carrier Spin Dynamics in InGaAs Quantum Dots
D. Yamazaki, S. Chen, J. Takayama and A. Murayama, Hokkaido Univ. (Japan)

PS-8-13
Improving Crystalline Quality of Sputtering Deposited MoS₂ Thin Film by Post-Sulfurization Annealing Using (t-C₄H₉)₂S₂
S. Ishihara¹, K. Suda¹, Y. Hibino¹, N. Sawamoto¹, T. Ohashi², S. Yamaguchi², K. Matsuura², H. Machida³, M. Ishikawa³, H. Sudoh³, H. Wakabayashi² and A. Ogura¹, ¹Meiji Univ., ²Tokyo Tech and ³Gas-phase Growth Ltd. (Japan)

PS-8-14
Large Effect of Etchant on Electrical Performance of Transferred CVD Graphene
T.W. Chen¹, Y.P. Hsieh¹ and M. Hofmann², ¹National Chung Cheng Univ. and ²NCKU (Taiwan)

PS-8-15
Improved Synthesis and Air Stability of Two-Dimensional Material GeH
N. Shao, R.R. Liang, C.C. Sun, L. Xiao, J. Wang and J. Xu, Tsinghua Univ. (China)

PS-8-16
Topography and Atomic Strain Deformation of Epitaxial Graphene on Si-terminated 6H-SiC Extended to the Few Microns Order
G. Rius¹, N. Mestres², Y. Tanaka¹, O. Eryu¹ and P. Godignon³, ¹Nagoya Inst. of Tech., ²ICMAB-CSIC and ³IMB-CNM-CSIC (Japan)

PS-8-17
Synthesis of Si-based Nanostructures by Extraction of Metallic Atoms from Silicides by Inositol Hexakisphosphate
K. Sasaki¹, K. Sano¹, X. Meng¹, H. Suzuki¹, T. Kobayashi², T. Kuno³ and H. Tatsuo¹, ¹Shizuoka Univ., ²Koba Tech. and ³Kankyo Science (Japan)

PS-8-18
Temperature Dependence of Electrical Transport Properties of La₄BaCu_{5-x}Co_xO_{13+δ} Conducting Oxide Thin Films
A. Tsuruta¹, Y. Tsujioka², Y. Yoshida², I. Terasaki^{1,2} and W. Shin¹, ¹AIST and ²Nagoya Univ. (Japan)

PS-8-19
Solvent Effect on Zinc Oxide Crystallites Shape using Submerged Photo-Synthesis
M. Jeem, K. Kawaguchi, A.M.R. Hamzah, J. Ishioka, S. Yatsu, T. Shibayama and S. Watanabe, Hokkaido Univ. (Japan)

PS-8-20
Study on Thermal Durability of AZO/Ag(Al)/AZO Transparent Conductive Film
Y. Sugimoto¹, K. Igarashi¹ and A. Kikuchi^{1,2}, ¹Sophia Univ. and ²Sophia Nanotech. Res. Center (Japan)

PS-8-21
Study on Microstructure of Gd₂O₃ and Nd₂O₃ Compound Film Formed by RF Magnetron Sputtering
Z. Wang, L. Xiao and J. Wang, Tsinghua Univ. (China)

PS-8-23
Epitaxial Growth of Yttrium Monoxide Thin Film
K. Kaminaga^{1,2}, R. Sei^{1,2}, T. Fukumura^{1,3} and T. Hasegawa^{1,3}, ¹Univ. of Tokyo, ²Tohoku Univ. and ³JST-CREST (Japan)

PS-8-24
Behavior of Si Atoms, Ge Atoms and Vacancies for Flash Lamp Annealing
A. Heya¹, N. Matsuo¹, S. Hirano¹, Y. Nakamura¹, T. Yokomori² and M. Yoshioka², ¹Univ. of Hyogo and ²USHIO Inc. (Japan)

PS-8-25
Low Temperature Liquid Phase Epitaxy of YBa₂Cu₃O₇ Films by the Molten KOH Method
S. Fumaki, Y. Yamada, R. Okunishi and Y. Miyachi, Shimane Univ. (Japan)

PS-8-26
Thermoelectric Properties of Yb₂Fe₃Co₄Sb₁₂ Prepared under High Pressure
Y. Chen, Y. Kawamura and C. Sekine, Murooran Inst. of Tech. (Japan)

PS-8-27
Effect of Fabrication Method on the Structural and Magnetic Properties of Copper Ferrite
S. Pongpudung, T. Kamwanna and V. Amornkitbamrung, Khon Kaen Univ. (Thailand)

PS-8-28 (Late News)
Chemical Vapor Deposition of Highly Resistive ZnO Films using Nonequilibrium N₂/O₂ Plasma Generated near Atmospheric Pressure
Y. Nose¹, T. Kiguchi¹, T. Yoshimura¹, A. Ashida¹, T. Uehara² and N. Fujimura¹, ¹Osaka Prefecture Univ. and ²Sekisui Chemical Co., LTD. (Japan)

Area 9: Physics and Applications of Novel Functional Devices and Materials	(11 papers)
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PS-9-1
Performance Enhancement of Calcium-doped Zinc Oxide Thin Film Transistors Fabricated on Glass at Low Temperature
W. Yu, D.D. Han, G.D. Cui, P. Shi, Y. Zhang, Y.Y. Cong, X.L. Zhou, L.L. Huang, X. Zhang, Y. Wang and S.D. Zhang, Peking Univ. (China)

PS-9-2
Oxygen Partial Pressure Dependence of Ti-Zn-O Thin-Film Transistors Fabricated on Flexible Plastic Substrate at Low Temperature
G.D. Cui, D.D. Han, W. Yu, P. Shi, Y. Zhang, L.L. Huang, Y.Y. Cong, X.L. Zhou, X.M. Zhang, S.D. Zhang, X. Zhang and Y. Wang, Peking Univ. (China)

PS-9-3
Characterization of Epitaxial Calcium Fluoride as a Dielectric Material for Ultra-thin Barrier Layers in Silicon Microelectronics
Y.Y. Illarionov^{1,2}, M.I. Vexler², V.V. Fedorov², S.M. Suturin², N.S. Sokolov² and T. Grasser¹, ¹TU Wien and ²Joﬀe Physical-Techn. Inst. (Austria)

PS-9-4
All Oxide All Solution-processed Active Matrix Thin-film Transistor for Electrophoretic Display Application
T.T. Phan^{1,2}, S. Inoue¹, H. Koyama³, Y. Takamura^{1,2} and T. Shimoda¹, ¹JAIST, ²JST-CREST and ³Toppaan Printing Co., Ltd. (Japan)

PS-9-5
Mesoscopic Blockade and Staircase Phenomena of Holes in DNA/Si-MOSFET by Gate Voltage Modulation
N. Matsuo¹, S. Nakamura¹, T. Takada¹, A. Heya¹, K. Yamana¹, T. Sato², S. Yokoyama² and Y. Omura³, ¹Univ. of Hyogo, ²Hiroshima Univ. and ³Kansai Univ. (Japan)

PS-9-6
A Quasi-ballistic Transport Model for Top- and Back-gated Graphene Nanoribbon Field-effect Transistors
G. Hu, S. Hu, L. Wang, R. Liu and L. Zheng, Fudan Univ. (China)

PS-9-7
A Concept of Heterogeneous Circuits with Epitaxial Tunnel Layer Tunnel FETs
J.H. Hung, P.Y. Wang, B.Y. Tsui and C.H. Yang, NCTU (Taiwan)

PS-9-8
Gate-Stacking Engineering for Insta Ge/SiO₂/SiGe MOS Devices
P.H. Liao¹, W.T. Lai², S.C. Luo¹, K.C. Yang¹, T. George¹ and P.W. Li², ¹National Central Univ. and ²NCTU (Taiwan)

PS-9-9
Novel Design of Electrostatic Lens Potential for Improving Bending Curvature and Transmission Probability of Drive Current for Vertical Body Channel MOSFET
M. Muraguchi^{1,2,3} and T. Endoh^{1,2,3}, ¹Tohoku Univ., ²CIES, Tohoku Univ. and ³JST-ACCEL (Japan)

PS-9-11
Geometry-dependent Phase/Stress and Electrical Resistivity in Nickel-Silicide Nanowires
C.C. Wang¹, Y.Y. Hsiao¹, I.H. Chen¹, W.T. Lai¹, T. George¹ and P.W. Li², ¹National Central Univ. and ²NCTU (Taiwan)

PS-9-12
Changes in Morphology and Local Conductance of GeTe-Sb₂Te₃ Superlattice Films on Silicon Made by Scanning Probe Microscopy in a Lithography Mode
L. Bolotov^{1,2}, T. Tada^{1,2}, Y. Saito^{1,2} and J. Tominaga^{1,2}, ¹AIST and ²JST-CREST (Japan)

Area 10: Organic Materials Science, Device Physics, and Applications	(12 papers)
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PS-10-1
Temperature Dependence Analysis of Printed Organic MOSFET
H. Zenitani¹, T.K. Maiti², T. Hayashi¹, Y. Tanimoto¹, K. Sato¹, L. Chen², H. Kikuchihara², M. Miura Mattausch² and H.J. Mattausch¹, ¹Hiroshima Univ. and ²HiSIM, Hiroshima Univ. (Japan)

PS-10-2
Control of Threshold Voltage in Organic Thin-film Transistors by Modifying Gate Electrode Surface with MoO_x Aqueous Solution and Its Application to Circuits
R. Shiwaku¹, Y. Yoshimura¹, Y. Takeda¹, K. Fukuda^{1,2}, D. Kumaki¹ and S. Tokito¹, ¹Yamagata Univ. and ²JST-PRESTO (Japan)

PS-10-3
Solution-Processed Hybrid Organic-Inorganic Complementary Thin-Film Transistor Inverter
H.J. Cheong, S. Ogura, K. Kuribara, M. Yoshida, H.. Ushijima, N. Fukuda and S. Uemura, AIST (Japan)

PS-10-4
Fabrication of Organic Field Effect Transistors Based on Printing Techniques and the Improvement of FET Properties by the Insertion of Solution Processable Buffer Layers
A. Kanamori and E. Itoh, Shinshu Univ. (Japan)

PS-10-5
All-Solution-process Red Phosphorescent and Blue Fluorescent Organic Light-emitting Diodes by Blade Coating
Y.F. Chang¹, H.F. Meng¹, H.W. Zan¹, H.W. Lin², K.T. Wong³, H.L. Huang⁴ and S.F. Horng², ¹NCTU, ²National Tsing Hua Univ., ³National Taiwan Univ. and ⁴e-Ray Optoelectronics Tech. Co., Ltd. (Taiwan)

PS-10-6
Novel Textile Actuator Having a Large Displacement Consisting of Electrospun Poly(DL-Lactic Acid) Fibrous Film and Its Mechanism
T. Nobeshima¹, Y. Ishii², H. Sakai³, S. Uemura¹ and M. Yoshida¹, ¹AIST, ²Toyohashi Univ. of Tech. and ³JAIST (Japan)

PS-10-7
Deposition Characteristics of Small Molecule Organic Thin Film (CBP:PBD:TPD:Ir(Mppy)₃) by Modified Electrospray Deposition
Y. Niinuma¹, D. Nishi¹, J. Ishino¹ and A. Kikuchi^{1,2}, ¹Sophia Univ. and ²Sophia Nanotech. Res. Center (Japan)

PS-10-8
Bis(thiophenyl)benzothiadiazole Derivatives as Hole-Transporting Red Emitters for Efficient Solution-Processed Pure Red Electroluminescent Devices
V. Promarak¹, A. Thangthong², S. Namuangruk², T. Sudyoadsuk¹, T. Kaewin², S. Jungsuttiwong² and A. Prachumrak¹, ¹Vidyasirimedhi Inst. of Sci. and Tech., ²Ubon Ratchathani Univ. and ³NANOTEC (Thailand)

PS-10-9 (Late News)
Lower Power Consumption Technique on Organic Circuits for Roll-to-roll Process.
K. Kuribara¹, K. Kakita², Y. Tanaka² and M. Yoshida¹, ¹AIST and ²Ube Indus., Ltd. (Japan)

PS-10-10 (Late News)
Achieving Low-Program Voltage and High-Stability in Controllable Organic Complementary Logic Circuits by Photoactive Gate Dielectric
T.T. Dao¹, H. Sakai², K. Ohkubo³, S. Fukuzumi⁴ and H. Murata², ¹Univ. of Transport and Communications, ²JAIST, ³Osaka Univ. and ⁴Ewha Womans Univ. (Vietnam)

PS-10-11 (Late News)
Molecular Dynamics and Electronic Structure Studies of Organic Semiconductors under Mechanical Stress
K. Yamakawa, W. Xie., T. Yanase, T. Nagahama and T. Shimada, Hokkaido Univ. (Japan)

PS-10-12 (Late News)
Achieving Efficient Solution-Processed Small Molecular Solar Cells via Non-halogenated Solvent
C.W. Chu^{1,2} and M.E. Farahat¹, ¹National Tsing Hua Univ. and ²Academia Sinica (Taiwan)

Area 11: Sensors and Materials for Biology, Chemistry and Medicine (13 papers)
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PS-11-1
IGZO Substrate for PH Detection in LAPS with High Photo Response
C.H. Chen, C.M. Yang, L.B. Chang, J.C. Wang and C.S. Lai, Chang Gung Univ. (Taiwan)

PS-11-2
Temperature-Lowered Plasma Treatment by Controlling Direction of Supplying Reactive Species for Biological Application
Y. Nakayama¹, S. Kumagai¹, H. Hashizume², T. Ohta³, M. Ito³, M. Hori² and M. Sasaki¹, ¹Toyota Tech. Inst., ²Nagoya Univ. and ³Meijo Univ. (Japan)

PS-11-3
A Friendly Portable 2D Chemical Imaging System
C. Ren¹, C.G. Lyu¹, H.L. Liu², Y.M. Chen², Y.C. Hsu², C.M. Yang² and C.S. Lai², ¹Tianjin Univ. and ²Chang Gung Univ. (China)

PS-11-4
High Sensitive Biosensor using Si Photonic Crystal Cavity Resonators
A.K. Sana, K. Honzawa, Y. Amemiya and S. Yokoyama, Hiroshima Univ. (Japan)

PS-11-5
Development of a Novel Device for Allergy Test Based on Semiconductor Principle
H.Y. Yang¹, A. Saito¹, T. Kajisa², Y. Yanase³ and T. Sakata¹, ¹Univ. of Tokyo, ²PROVIGATE Inc. and ³Hiroshima Univ. (Japan)

PS-11-6
Nanosphere Lithography (NSL) on Au Nanopatterned Electrodes for Electrochemical DNA Detection
A. Purvvidyantri¹, C.H. Chen², C.C. Chiou¹, Y.C. Tian³ and C.S. Lai¹, ¹Chang Gung Univ., ²National Taiwan Univ. of Sci. and Tech. and ³Chang Gung Memorial Hospital (Taiwan)

PS-11-7
Highly Sensitive pH-EGFET Sensors with Oxygen-Plasma-Treated Reduced Graphene Oxide Films Sprayed on the Reverse Pyramid Substrate
Y.R. Li, S.H. Chang, W.L. Tsai, C.T. Chang and H.C. Cheng, NCTU (Taiwan)

PS-11-8
Characteristics of N₂/H₂ Annealed Ni-Co Nanowires Upon Immobilized Affinity of Penta-histidine-tagged Protein
C.-Y. Ho, T.-H. Lin and Y.-J. Chang, Chung Yuan Christian Univ. (Taiwan)

PS-11-9
A Fluorescent Arrayed Biosensor Using Liposome Encapsulating Calcein for Discrimination of Different Target Proteins by Principal Component Analysis
R. Imamura¹, Z. Zhang¹, T. Shimanouchi², N. Murata¹, K. Yamashita¹, M. Fukuzawa¹ and M. Noda¹, ¹Kyoto Inst. of Tech. and ²Okayama Univ. (Japan)

PS-11-10
The Annealing Effect of BaSrTiO₃ Membrane in O₂ and N₂ Ambient for Electrolyte-Insulator-Semiconductor
Y.L. Su, C.H. Kao, C.F. Lin, C.W. Chang, C.L. Chang, S.W. Chang and Y.X. Huang, Chang Gung Univ. (Taiwan)

PS-11-11
Controlled Decoration of Double Junction N⁺/N⁻/N⁺ Polysilicon Nanobelt Device with Platinum for Hydrogen Gas Sensor Application
N.A. Tran, C.H. Sang, F.M. Pan and J.T. Sheu, NCTU (Taiwan)

PS-11-12 (Late News)
Cross-Talk Immunity of Gold-Nanoparticle Incorporated PEDOT:PSS Pressure Sensors with 2×2 Cross-Point Array Structure
R.S. Karmakar¹, Y. Fu¹, S.H. Chen¹, J.C. Wang¹, Y.J. Lu², C.Y. Huang², K.C. Wei² and C.S. Lai¹, ¹Chang Gung Univ. and ²Chang Gung Memorial Hospital (Taiwan)

PS-11-13 (Late News)
Improvement of Filter-less Fluorescence Sensor by the Surface Planarization of Polysilicon Photogate
Y.J. Choi, K. Takahashi, M. Matsuda, T. Hizawa, Y. Moriwaki, F. Dasai, Y. Kimura, I. Akita, T. Iwata, M. Ishida and K. Sawada, Toyohashi Univ. of Tech. (Japan)

Area 12: Spintronics Materials and Devices (20 papers)
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PS-12-1
Anti-Damping Torque Engineering in Trilayer Spin-Hall System
G. Gupta, M.B.A. Jalil and G. Liang, NUS (Singapore)

PS-12-2
Enhancement of Gilbert Damping in Trilayer Synthetic Antiferromagnets via Dynamic Exchange Interactions
T. Chiba¹, G.E.W. Bauer^{1,2,3} and S. Takahasi¹, ¹IMR, Tohoku Univ., ²WPI-AIMR, Tohoku Univ. and ³Kavli Inst. of NanoScience Delft Univ. of Tech. (Japan)

PS-12-3
A Pulse Current Synchronization Scheme for Spin Torque Nano Oscillators
K. Nakada¹, K. Miura² and T. Kimura³, ¹Hiroshima City Univ., ²Kwansei Gakuin Univ. and ³Kyushu Univ. (Japan)

PS-12-4
Spin Transport in Magnetic Tunnel Junctions with the Insertion of [6]Cyclo-2,7-naphthylenes Organic Semiconductor
K. Suzuki¹, T. Izumi^{2,3}, X. Zhang¹, A. Sugihara¹, S.T. Pham¹, H. Taka^{2,3}, S. Sato^{1,2}, H. Isobe^{1,2} and S. Mizukami¹, ¹Tohoku Univ., ²JST-ERATO and ³KONICA MINOLTA, Inc. (Japan)

PS-12-5
Bias Voltage Dependence of the Spin-dependent Tunneling Conductance of Co₂(Mn,Fe)Si-Based Magnetic Tunnel Junctions Exhibiting Giant Tunneling Magnetoresistances
K. Moges, B. Hu, H.x. Liu, T. Uemura and M. Yamamoto, Hokkaido Univ. (Japan)

PS-12-6
Temperature Dependence of Spin-Dependent Tunneling Conductance of Magnetic Tunnel Junctions with Highly Spin-Polarized Electrodes
B. Hu, Kidist. Moges, H.x. Liu, Y. Honda, T. Uemura and M. Yamamoto, Hokkaido Univ. (Japan)

PS-12-7
Exchange Bias Effects in Ni₂MnAl/Ferromagnet Film Bilayers
T. Kubota, T. Tsuchiya, T. Sugiyama and K. Takanashi, Tohoku Univ. (Japan)

PS-12-8
Theoretical Sensitivity in Magnetic Field Sensors using a Spin-torque Oscillator
Y. Suzuki^{1,2}, A. Tulapurkar³, H. Tomita¹, E. Tamura¹, H. Kubota², S. Miwa¹, A. Fukushima² and S. Yuasa², ¹Osaka Univ., ²AIST and ³IIT Bombay (Japan)

PS-12-9
Nanoscale Magneto-Resistance Sensors with Improved Sensitivity using Resonant Tunneling Magnetic Tunnel Junctions
N. Chatterji, A. Sharma, A. Tulapurkar and B. Muralidharan, IIT Bombay (India)

PS-12-10
Experimental Demonstration of Long-Distance Propagation of a Surface Plasmon on the Surface of a Ferromagnetic Metal
V. Zayets, H. Saito, S. Yuasa and K. Ando, AIST (Japan)

PS-12-11
Influence of Oxygen Partial Pressure on Electrical and Magnetic Characteristics of Spinel CoFe₂O₄ Thin Films
M. Araki, H. Kajita, N. Takahashi, T. Yanase, T. Shimada, H. Ohta and T. Nagahama, Hokkaido Univ. (Japan)

PS-12-12
Magnetic and Electronic Properties of Epitaxial Mn₂CoAl Films
K. Ueda, S. Hirose, S. Aichi, T. Hajiri and H. Asano, Nagoya Univ. (Japan)

PS-12-13
Crystallographic Properties of L1₀ Ordered FeNi Thin Films Fabricated by Sputtering and Rapid Thermal Annealing
M. Mizuguchi¹, T.Y. Tashiro¹, T. Koganezawa² and K. Takanashi¹, ¹Tohoku Univ. and ²SPRING-8/JASRI (Japan)

PS-12-14
Experimental Analysis of Shubnikov-De Haas Oscillation for Slightly Asymmetric InGaAs/InAlAs Double Quantum Wells
H. Chen¹, T. Matsuura¹, A. Sawada¹, T. Yamashige¹, B. Liu¹, H. Sugiyama², Y. Sekine² and T. Koga¹, ¹Hokkaido Univ. and ²NTT Corp. (Japan)

PS-12-15
Real Space Analysis of Classical Diffusion and Weak Localization of Electrons in Mesoscopic Systems from Boltzmannian Picture
A. Sawada and T. Koga, Hokkaido Univ. (Japan)

PS-12-16
Electron G-factor Engineering in GaAs Quantum Nano-Disks Fabricated by Defect-Free Neutral Beam Etching Process
Y.C. Tsai¹, L.W. Yang¹, Y. Li¹, O. Voskoboinikov¹, A. Higo², A. Murayama³ and S. Samukawa², ¹NCTU, ²Tohoku Univ. and ³Hokkaido Univ. (Taiwan)

PS-12-17
Transient Analysis of Oblique Hanle Signals Observed in GaAs
Z.c. Lin, M. Yamamoto and T. Uemura, Hokkaido Univ. (Japan)

PS-12-18
Influence of Si Surface on Spin Accumulation and Transport Signals in CoFe/MgO/n⁺-Si Junctions
M. Ishikawa¹, H. Sugiyama¹, T. Inokuchi¹, K. Hamaya², N. Tezuka³ and Y. Saito¹, ¹Toshiba Corp., ²Osaka Univ. and ³Tohoku Univ. (Japan)

PS-12-19
Temperature Dependences of Spin-injection Dynamics and Spin-polarized Electroluminescence in InGaAs Quantum Dots
Y. Nomura¹, Y. Akei¹, J. Takayama¹, T. Kiba², A. Subagyo¹, T. Yamamura¹, D. Yamazaki¹, K. Sueoka¹ and A. Murayama¹, ¹Hokkaido Univ. and ²Kitami Inst. of Tech. (Japan)

PS-12-20
Spin Depolarization Induced by Low Electric Fields in Undoped InGaAs/AlGaAs Multiple Quantum Well
Y.H. Chen, L.P. Zhu and Y. Liu, Chinese Academy of Sciences (China)

Area 13: Applications of Nanotubes, Nanowires, and Graphene

(22 papers)

PS-13-1
Direct Observation of Evolution in Graphene Layers by Electrical Properties
C.W. Huang, J.Y. Chen and W.W. Wu, NCTU (Taiwan)

PS-13-2
Bandgap Engineering of Graphene by Mean of Adsorption of Defective Graphene
K. Kishimoto and S. Okada, Univ. of Tsukuba (Japan)

PS-13-3
Al₂O₃/HfO₂/Al₂O₃/Graphene Charge Trap Flash Device with a Self-aligned Gate
K.H. Lee and O.H. Kim, POSTECH (Korea)

PS-13-4
Radical Spin Interaction of Graphene Flakes Embedded into h-BN Sheet
M. Maruyama and S. Okada, Univ. of Tsukuba (Japan)

PS-13-5
First-Principles Calculations for Diffusion Mechanism of Li Atom from Li(EC)₄ to Interlayer of Graphite with Hydrogen/Carbonylic Edge Terminations
T. Kawai^{1,2}, S. Okada² and M. Otani¹, ¹NEC Corp., ²Univ. of Tsukuba and ³AIST (Japan)

PS-13-6
Study of the Electronic Properties and Strain sensitivity of Chemical Vapor Deposition-Grown Graphene from C₂H₂
M. Yang, S. Sasaki, M. Ohnishi, K. Suzuki and H. Miura, Tohoku Univ. (Japan)

PS-13-8
Thermal Interface Materials with Vertically-aligned Carbon Nanotubes and Their Thermal Properties
S. Hirose¹, M. Norimatsu¹, K. Suzuki¹, Y. Yagishita¹, Y. Suwa², T. Kurosawa², K. Kawamura², Y. Mizuno¹, D. Kondo¹ and T. Iwai¹, ¹Fujitsu Labs. Ltd. and ²Shinko Electric Industries Co., Ltd. (Japan)

PS-13-9
Competition and Cooperation between External and Internal Electric Fields for Carrier Injection in Carbon Nanotubes with Defects
U. Ishiyama¹, N.T. Cuong² and S. Okada¹, ¹Univ. of Tsukuba and ²NIMS (Japan)

PS-13-10
Solution Processible Metal Nanoparticle Embedded Reduced Graphene Oxide for Stretchable and Conductive Electrode
Y. Yoon¹ and H.L. Lee^{1,2}, ¹IBS Sungkyunkwan Univ. and ²Sungkyunkwan Univ. (Korea)

PS-13-11
Mechanisms of Polarization Switching in Graphene Oxide and Poly(Vinylidene Fluoride)-Graphene Oxide Films
Z.Y. Jiang¹, G.P. Zheng¹, K. Zhan² and Z. Han^{1,2}, ¹The Hong Kong Polytechnic Univ. and ²USST (China)

PS-13-12
Energetics of H₂O Encapsulated in Fullerenes under an Electric Field
J. Sorimachi and S. Okada, Univ. of Tsukuba (Japan)

PS-13-13
Top-Gated Epitaxial Bilayer MoSe₂ Transistors on AlN Wafers & the Impact of Top-down Process-Induced Damage
M. Manfrini¹, S. Sutar¹, S. Brems¹, P. Tsipas², K.E. Aretoulis², E. Xenogiannopoulou², A. Dimoulas², A.C. Mocuta¹, I.P. Radu¹ and A. Thean¹, ¹IMEC and ²NCSR Demokritos (Belgium)

PS-13-14
XPS Study of HfO₂ Growth on 2H-MoS₂ Substrate
C.P. Chen¹, S.W. Ong², J.W. Chai³, Z. Zhang³, S.J. Wang³, J.S. Pan³ and E.S. Tok^{1,2}, ¹NUS, ²Yale-NUS College and ³Inst. of Material Res. and Eng. (Singapore)

PS-13-15
Electrical and Optical Properties of Co-doped and Undoped MoS₂ Crystals
C.C. Huang¹, T.S. Ko¹, D.Y. Lin¹, Y.J. Ruan¹ and Y.S. Huang², ¹National Univ. of Changhua Edu. and ²National Taiwan Univ. of Sci. and Tech. (Taiwan)

PS-13-16
MoS₂ FET based Oxygen Sensors with Gate Voltage Stress Induced Performance Enhancement
Y. Tong, Z. Lin, J.T.L. Thong, D.S.H. Chan and C. Zhu, NUS (Singapore)

PS-13-17
Theoretical Study of Multiatomic Vacancies in Hexagonal Boron Nitride
S. Urasaki and H. Kageshima, Shimane Univ. (Japan)

PS-13-18
Growth and Characterization of Wurtzite InP/AlInP Core-Shell Nanowires
F. Ishizaka¹, Y. Hiraya¹, K. Tomioka^{1,2} and T. Fukui¹, ¹Hokkaido Univ. and ²JST-PRESTO (Japan)

PS-13-19
Hybrid Nanoimprint SiNW-based Solar Cell Fabrication with Efficiency Enhancement by Hydrogen Annealing
W. Jevasuwan, K. Nakajima, Y. Sugimoto and N. Fukata, NIMS (Japan)

PS-13-20
Stability and Electronic Structures of Group IV Semiconductor Alloy Nanosheets: a First Principles Study
T. Akiyama, K. Nakamura and T. Ito, Mie Univ. (Japan)

PS-13-21
Fundamental Strategy to Succeed a Vapor-Liquid-Solid Nanowire Growth
T. Yanagida, K. Nagashima, H. Yong, F. Zhuge, M. Kanai and A. Klamchuen, Kyushu Univ. (Japan)

PS-13-22
Axial Strain Effects on Phonon Thermal Transport in Silicon Nanowires
J. Hattori, V. Poborchii and T. Tada, AIST (Japan)

PS-13-23 (Late News)
Graphene Nanoribbon Field Effect Transistor Designing from Numerical Simulations
K. Takashima, S. Konabe and T. Yamamoto, Tokyo Univ. of Science (Japan)

Area 14: Power Devices and Materials

(19 papers)

PS-14-1
Minimization of Reverse Recovery Charge and Forward Voltage of Silicon Pin Diodes
Y. Yamashita and S. Machida, Toyota Central R&D Labs., Inc. (Japan)

PS-14-2
The Resistance Effect on Turn-on Speed of Resistor Assisted Trigger SCR Stacking Structure
S.S. Yen¹, C.C. Fan¹, Y.P. Lan¹, C.Y. Chang¹, Y.C. Chiu¹, Z.W. Jiang², S.C. Chang², L.Y. Hung² and C.C. Tsai², ¹NCTU and ²Himax Tech. Inc. (Taiwan)

PS-14-3
Impact of 3D Stacking Silicon on Diamond Substrate for the ESD Protection Device
Y. Ikeda, K. Nakagawa and S. Matsumoto, Kyushu Inst. of Tech. (Japan)

PS-14-4
The Heat Performance Study of Nanocrystal Diamond Film Used in a Thin Film Device
S. Duangchan¹, Y. Koishikawa¹, R. Shirahama¹, K. Oishi¹, A. Baba¹, S. Matsumoto¹ and M. Hasegawa², ¹Kyushu Inst. of Tech. and ²AIST (Japan)

PS-14-5
Transport Characteristics of Minority Carriers in 4H-SiC/Si Heterojunction Bipolar Transistor Structures Fabricated by Surface Activated Bonding
J. Liang¹, S. Shimizu¹, S. Nishida¹, N. Shigekawa¹ and M. Arai², ¹Osaka City Univ. and ²New JRC (Japan)

PS-14-6
Improved Electrical Properties of 4H-SiC MOS Devices with High Temperature Thermal Oxidation
H. Xu^{1,2}, Q. Yang¹, M. Zhao¹, S. Wang¹, Z. Jin¹, X. Liu¹, A. Chanthaphan², Y. Cheng², T. Hosoi², T. Shimura² and H. Watanabe², ¹IMECAS and ²Osaka Univ. (China)

PS-14-7
Removal of Near-Interface Oxide Traps at SiO₂/SiC Interface by Post-Oxidation Annealing in Reducing Ambient
H. Kajifusa, H. Hirai, Y. Fujino and K. Kita, Univ. of Tokyo (Japan)

PS-14-8
Charge Distribution in Termination Area of 4H-SiC Diodes Analyzed by Measuring Depletion-layer Capacitance
H. Matsushima, H. Okino, K. Mochizuki and R. Yamada, Hitachi Ltd. (Japan)

PS-14-9
Investigation of 4H-SiC IGBT Turn-off Performance for Achieving Low Power Loss
D. Navarro¹, I. Pesic¹, Y. Morikawa¹, Y. Furui¹ and M. Miura Mattausch², ¹Silvaco Japan and ²Hiroshima Univ. (Japan)

PS-14-10
Characterization of Near-Interface Oxide Trap Density in SiC MOS Capacitors by Transient Capacitance Measurements at Various Temperatures
Y. Fujino and K. Kita, Univ. of Tokyo (Japan)

PS-14-11
Mapping of Si/SiC Hetero p-n Junctions Using Scanning Internal Photoemission Microscopy
M. Shingo¹, J. Liang², N. Shigekawa², M. Arai³ and K. Shiojima¹, ¹Univ. of Fukui, ²Osaka City Univ. and ³New JRC (Japan)

PS-14-12
Photoemission Spectroscopy Measurements of p⁺-Si/n-SiC and n⁺-Si/n-SiC Junctions by Surface Activated Bonding
N. Shigekawa¹, J. Liang², M. Shingo², M. Arai³ and K. Shiojima², ¹Osaka City Univ., ²Univ. of Fukui and ³New JRC (Japan)

PS-14-13
Special Features in Stress Degradation of SiC-MOSFETs Observed in I-V Characteristics
E. Murakami, K. Oda and T. Takeshita, Kyushu Sangyo Univ. (Japan)

PS-14-14
Heteroepitaxial Growth of Diamond on 3C-SiC/Si Substrates by Antenna-Edge Microwave Plasma CVD
T. Suto¹, J. Yaita^{1,2}, T. Iwasaki^{1,2,3}, M. Natal⁴, S.E. Saddow⁴ and M. Hatano^{1,2,3}, ¹Tokyo Tech, ²JST-CREST, ³JST-ALCA and ⁴Univ. of South Florida (Japan)

PS-14-15
Trench-channel MOSFET using C-H Diamond Surface
T. Saito, M. Kobayashi, T. Yamada, D. Xu, Y. Kitabiyashi, D. Matsumura, M. Inaba, A. Hiraiwa and H. Kawarada, Waseda Univ. (Japan)

PS-14-16
Solution Growth of AlN Single Crystal on Sapphire using Multi-Component Solvent Designed by Thermodynamic Calculation
S. Harada, M. Nagaya, S. Watanabe, M. Chen, Y. Takeuchi, K. Aoyagi, M. Tagawa and T. Ujihara, Nagoya Univ. (Japan)

PS-14-17 (Late News)
A 150 a SiC VMOSFET with 6 x 6 mm² Chip Size on a 150 mm C-face in-house Epitaxial Wafer
Y. Saitoh, H. Itoh, K. Wada, M. Sakai, T. Horii, K. Hiratsuka, S. Tanaka and Y. Mikamura, Sumitomo Electric Industries, Ltd. (Japan)

PS-14-18 (Late News)
Investigation of Conventional Bipolar Logic Technologies in 4H-SiC for Harsh Environment Applications
H. Elgabra, A. Siddiqui and S. Singh, Khalifa Univ. of Sci., Tech. & Res. (UAE)

PS-14-19 (Late News)
Investigation of Deep Levels in Diamond Based Radiation Detector by Transient Charge Spectroscopy with Focused Heavy Ion Microbeam
Y. Ando^{1,2}, Y. Kambayashi^{1,2}, W. Kada¹, S. Onoda², T. Makino², S. Sato², H. Umezawa³, Y. Mokuno³, S. Shikata¹, O. Hanaizumi¹, T. Kamiya² and T. Ohshima², ¹Gunma Univ., ²JAEA, ³AIST and ⁴Kwansei Gakuin Univ. (Japan)

Area 15: Photovoltaic Materials and Devices	(20 papers)
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PS-15-1
Exciton and Bandgap Energies of Hybrid Perovskite CH₃NH₃PbI₃
Y. Nakamura¹, J. Sano¹, T. Matsushita^{1,3}, Y. Kiyota², Y. Udagawa², H. Kunugita^{2,3}, K. Ema^{2,3} and T. Kondo^{1,3,4}, ¹Univ. of Tokyo, ²Sophia Univ., ³JST-ALCA and ⁴RCAST, Univ. of Tokyo (Japan)

PS-15-2
Optical Pumped Lasing in Solution Processed Perovskite Semiconducting Materials: Self Assembled Microdisk Lasing
F. Sasaki, H. Mochizuki, Y. Zhou, Y. Sonoda and R. Azumi, AIST (Japan)

PS-15-3
Shape-Controlled Preparation of MAPbI₃ Nanoparticles by Ionic Liquid-Assisted Simple Spin-coating Method with Tunable Optical Absorption
Md. Shahiduzzaman, K. Yamamoto, Y. Furumoto, T. Kuwabara, K. Takahashi and T. Taima, Kanazawa Univ. (Japan)

PS-15-4
Field Test of Dye-Sensitized Solar Cells by Utilizing a Power Delivery CMOS Integrated Circuits
J. Miyamoto¹, M. Sato¹, H. Itoh¹, M. Tanaka¹, A. Kato¹, S. Hasegawa¹, Y. Suzuki² and F. Munakata², ¹Chubu Univ. and ²Tokyo City Univ. (Japan)

PS-15-5
Efficiency Enhancement of Dye-sensitized Solar Cells by Flower-like Zinc Oxide
F.I. Lai¹, M.Y. Hsieh² and S.Y. Kuo², ¹Yuan Ze Univ. and ²Chang Gung Univ. (Taiwan)

PS-15-6
Organic Ultraviolet Photodetectors with m-MTDATA:LiF Nanocomposite Layer
R.W. Chuang¹, P.Y. Su¹ and C.H. Chen², ¹NCKU and ²Cheng Shiu Univ. (Taiwan)

PS-15-7
First-principles Study of Defect Formation in Photovoltaic Semiconductor Cu₂SnS₃
H. Nishihara, T. Maeda, A. Shigemi and T. Wada, Ryukoku Univ. (Japan)

PS-15-8
A Look into Plasmonic Energy Transfer in CIGS Solar Cells via Ultrabroadband Femtosecond Pump-probe Spectroscopy
J.X. Li¹, S.C. Chen¹, A. Yabushita¹, S.H. Tang¹, D.P. Tsai², H.C. Kuo¹, K.H. Wu¹ and T. Kobayashi¹, ¹NCTU and ²Academia Sinica (Taiwan)

PS-15-9
Investigation of the Optical Absorption in Si/SiO₂ Superlattice for the Application to Solar Cells
S. Yamada¹, M. Konagai^{1,2} and S. Miyajima³, ¹JST, ²Tokyo City Univ. and ³Tokyo Tech (Japan)

PS-15-10
Si Nanofilm Efficient UV Solar Absorber
V. Poborchii¹, Y. Morita¹, T. Tada¹, P. Geshev², Z. Utegulov³ and A. Volkov³, ¹AIST, ²Inst. of Thermophysics of the Russian Academy of Sciences and ³Nazarbayev Univ. (Japan)

PS-15-11
Hydrogenated Nanocrystalline Cubic Silicon Carbide/c-Si Heterojunction Solar Cell with Triple Anti-Reflection Coating
E.O. Ateto and S. Miyajima, Tokyo Tech (Japan)

PS-15-12
A New Interdigitated Nanopillar HIT Solar Cell with 26.09% Efficiency Achieved by Using Silicon-Carbide-based Window Layer
C.C. Lai, J.T. Lin, T.H. Huang, J.M. Syu and B.C. Yan, National Sun Yat-sen Univ. (Taiwan)

PS-15-13
Development of Wider Bandgap n-type a-SiO_x:H for High Efficiency a-Si:H Single Junction and a-Si:H/a-Si_{1-x}Ge_x:H Tandem Solar Cells
P.W. Chen, L.H. Lai, C.H. Hsu and C.C. Tsai, NCTU (Taiwan)

PS-15-14
Local Surface Potential on Amorphous Silicon Thin Film Solar Cells by Kelvin Force Microscope
T. Itoh, T. Ito, H. Kuriyama and S. Nonomura, Gifu Univ. (Japan)

PS-15-15
Detailed-Balance-Limit Efficiencies of Solar Cells with Intermediate Bands and Carrier Multiplication
K. Tanabe, Kyoto Univ. (Japan)

PS-15-16
A Simple Optical Model Well Explains Plasmonic-Nanoparticle-Enhanced Spectral Photocurrent in Optically Thin Solar Cells
K. Tanabe, Kyoto Univ. (Japan)

PS-15-17
InGaP/GaAs Heterojunction Phototransistor Powered by an On-Chip GaAs Solar Cell for Energy Harvesting
P.H. Than, K. Uchida and S. Nozaki, Univ. of Electro-Communications (Japan)

PS-15-18 (Late News)
Behavior of the Potential-Induced Degradation for Photovoltaic Modules Fabricated using Flat Mono-Crystalline Silicon Cells with Different Surface Orientations
S. Yamaguchi¹, A. Masuda² and K. Ohdaira¹, ¹JAIST and ²AIST (Japan)

PS-15-19 (Late News)
Degradation of Backsheets for Crystalline Photovoltaic Modules under Damp Heat
D. Kim, W. Hong and C. Oh, Korea Electronics Technology Institute (Korea)

PS-15-20 (Late News)
Optimization of Etching Paste Process by Screen Printing for Recycling Crystalline Silicon Solar Wafer from End-of-life Photovoltaic Modules
J. Shin and J. Jeong, Korea Electronics Technology Institute (Korea)